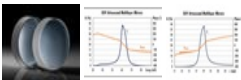


25.4mm Dia. x 500mm EFL, 19nm (65eV), 5° EUV/XUV Attosecond Multilayer Concave Mirror

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UltraFast Innovations (UFI) EUV/XUV Attosecond Multilayer Mirrors



Stock **#16-767** ☐ In Stock



1



C\$3,087.00

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Diameter (mm):
25.40 ±0.13

Substrate: ☐
[Fused Silica](#) (Corning 7980)

Back Surface: Commercial Polish
Coating Specification: Rs > 38% @ 65eV/19nm
Coating: EUV Multilayer (19nm)
Angle of Incidence (°): 5
Clear Aperture (%): 80
Design Wavelength DWL (nm): 19
Edges: Fine Ground
Surface Roughness (Angstroms): <1
Type: Concave Mirror
Center Energy (eV): 65 ±2
Bandwidth (eV): 6
Supported Pulse Duration: 330 attoseconds
Edge Thickness ET (mm): 6.35 ±0.20
Effective Focal Length EFL (mm): 500.00
Radius of Curvature (mm): 1,000.00
Radius R₁ (mm): 1,000.00
Irregularity (P-V) @ 632.8nm: λ/10

Regulatory Compliance

RoHS 2015: Compliant
Certificate of Conformance: View
Reach 235: Compliant